Dmetrisis Film Metrology & More...

FR-pOrtable: USB-powered film characterization tool at the Point-of-Need

FR-pOrtable is a unique miniaturized solution for accurate & precise non-destructive characterization of transparent and semi-transparent single films or stack of films.

With **FR-pOrtable** the user can perform reflectance and transmittance measurements in the 380-1020nm spectral range.

Applications

- Universities & Research labs
- **Semiconductors** (Oxides, Nitrides, Si, Resists, etc.)
- MEMS devices
 (Photoresists, Si membranes, etc.)
- o LED
- Data Storage
- Hard/Soft coatings on curved substrates
- **Polymer coatings,** adhesives, etc.
- Biomedical (parylene, balloon wall thickness, etc.)
- And more...
 (contact us with your requirements)



The compact size of **FR-pOrtable** and the custom designed reflection probe, guarantee highly accurate and repeatable measurements.

FR-pOrtable, can be either mounted on the supplied stage or can be easily transformed to a handheld thickness measurement tool to be placed over the sample under characterization.

FR-pOrtable is the only optical characterization tool for in-field applications.

Features

- Thickness measurement range: 12nm to 90 μ m
- Refractive Index (n & k) calculation
- Broad Spectral Range: 380nm 1020nm
- USB powered
- Portable

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Reflectance, Transmittance, Absorption and Color parameters

Specifications



Dimensions

300mm x 110mm x 40mm⁵

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Accessories

At-the-Field adaptor: For measurements at the Point-of-Need.
 Transmittance module: For the measurement of transmittance & absorbance spectra of coatings, coating thickness etc.
 Manual X-Y stage: For the characterization of coatings at multiple positions (manual movement)

Principle of Operation

White Light Reflectance Spectroscopy (WLRS) measures the amount of light reflected from a film or a multilayer stack over a range of wavelengths, with the incident light normal (perpendicular) to the sample surface.

The measured reflectance spectrum, produced by interference from the interfaces is being used to determine the thickness, optical constants (n & k), etc. of free-standing and supported (on transparent or partially/fully reflective substrates) stack of films.



*Specifications are subject to change without any notice, ¹Measurements compared with a calibrated spectroscopic ellipsometer and XRD, ²Average of standard deviation of mean value over 15 days. Sample: 1micron SiO₂ on Si wafer, ³Standard deviation of 100 thickness measurements. Sample: 1micron SiO₂ on Si wafer, ⁴2*Standard-Deviation of daily average over 15 days. Sample: 1micron SiO₂ on Si wafer, ⁵Without the stage